



1. Title:	Nikon EUVL development progress update
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3. Abstract body:

Updated progress on the development of Nikon's alpha EUV exposure tool named as EUV1 will be presented.

In the EUVA project, we have developed new polishing technologies; ion-beam figuring (IBF) and elastic emission machining (EEM), new high-precision interferometers for aspheric surface metrology, and EUV wavefront metrology system (EWMS) using New Subaru synchrotron source at University of Hyogo. Using these technologies, we developed a prototype of EUV projection optics. Polishing and coating of mirrors for the prototype optics have finished and adjustment of optical housing is now on going. And also we have already the started fabrication of projection optics for EUV1. Mirror polishing is in the final phase. Updated status of the optics will be presented in the conference.

Nikon has already completed EUV1 module parts fabrication and got into sub-assembly phase of all modules to meet tool development schedule. EUV1 tool development program has been proceeding along with mask, resist, and other infrastructure developments. Nikon announces that EUV1 tool is scheduled to be delivered in 1st half of 2007. Development of production tool dubbed EUV2 is also considered.